### **Supporting Information**

# Hierarchical Architecture of Metallic VTe<sub>2</sub>/Ti<sub>3</sub>C<sub>2</sub>T<sub>x</sub> MXene Heterostructure for Supercapacitor Applications

Sree Raj K A, <sup>1</sup> Narad Barman <sup>2</sup>, Sithara Radhakrishnan <sup>1</sup>, Ranjit Thapa <sup>2</sup>, and Chandra Sekhar Rout\*,<sup>1</sup>

<sup>1</sup> Centre for Nano and Material Science, Jain University, Jain global campus, Jakkasandra, Ramanagaram, Banglore - 562112, India.

<sup>2</sup> Department of Physics, SRM University – AP, Amaravati 522 240, Andhra Pradesh, India.

\*Corresponding author: csrout@gmail.com, r.chandrasekhar@jainuniversity.ac.in (CSR);

#### **Electrochemical Calculations**

Three electrode configuration-

Specific capacitance  $(C_{sp})$  from cyclic voltammetry;

$$Csp = \frac{Area \ of \ CV \ curve}{2 * m * \vartheta * \Delta V} \tag{S1}$$

Where, m is the mass of active material, v is the scan rate and  $\Delta V$  is the potential window. Specific capacitance ( $C_{sp}$ ) from galvanostatic charge discharge;

$$Csp = \frac{i * \Delta t}{m * \Delta V} \tag{S2}$$

Where, i is the applied current,  $\Delta t$  is the discharge time.

*Charge balance equation;*<sup>1</sup>

$$\frac{m_+}{m_-} = \frac{C_- * \Delta V_-}{C_+ * \Delta V_+} \tag{S3}$$

Specific capacitance  $(C_{sp})$  of ASC from galvanostatic charge discharge;

$$Csp = \frac{i * \Delta t}{m * \Delta V} \tag{S4}$$

Energy density of ASC;

$$E_D = \frac{1}{2}CV^2 \tag{S5}$$

Where, C is specific capacitance of ASC, V is the working window of ASC. *Power density of ASC;* 

$$P_D = \frac{E_D}{\Delta t} \tag{S6}$$

# **Supporting Figures**



**Figure S1**: Low (a) and high (b) resolution FESEM images of etched MXene showing the accordion like morphology.



Figure S2: EDS element mapping of VTX80 sample showing the uniform distribution of V,

Te, Ti, and C.



**Figure S3**: (a) TEM image of VTX 80, (b, c) HRTEM images of VTX 80 showing lattice fringes of (004) plane of  $Ti_3C_2$  MXene and (002) plane of VTe<sub>2</sub> and (d) corresponding SAED pattern.



Figure S4: XPS survey spectrum of VTX80 showing the presence of V 2p, Te 3d. C 1s and

Ti 2p species.



rates, GCD curves of (d)  $VTe_2$ , (e) VTX40 and (f) VTX120 in different specific currents ranging from 0.25 to 4 A/g.



Figure S6: (a) Cyclic voltammogram and (b) GCD profile of MXene.



Figure S7: Comparison of the CV curves of VTX80 electrode in  $0.5M \text{ K}_2\text{SO}_4$  and 0.5M KCl (analysed using a conventional glassy carbo electrode).



**Figure S8:** (a) Comparative CV profile of  $VTe_2$ , MXene and VTX80 at 100 mV/s, (b) Cyclic stability of  $VTe_2$ , MXene and VTX80.  $VTe_2$  and MXene have a cyclic stability of 71.3% and 66.6% respectively, VTX80 on the other hand showed an improved cyclic stability of 83.3%.

Scan Rate (mV/s)	Capacitive Contribution (%)	Diffusive Contribution (%)
10	81.8	18.2
20	82.9	17.1
40	83.6	16.4
60	85.8	14.2
80	89.2	10.8
100	90.1	9.9
200	97.2	2.8

**Table S1:** The segregated capacitive and diffusive contributions obtained by deconvolutingCV using Dunn method.



Figure S9: (a-b) Trasatti plots.

Sample	$R_{s}(\Omega)$	$R_{ct}(\Omega)$
VTe <sub>2</sub>	8.07	9.43
VTX40	5.5	18.51
VTX80	2.62	5.48
VTX120	5.11	9.44

Table S2: The R<sub>s</sub> and R<sub>ct</sub> values of all the samples obtained from Nyquist plot.



**Figure S10:** Characterization of VTX80 electrode after electrochemical analysis. (a) XRD pattern of VTX80 electrode before and after. A notable peak  $\sim$ 31° which can be assigned to the (101) plane of VTe (JCPDS: 89-7104). XRD pattern of VTX80 electrode shows sharp intense doublet of Ni foam which has been used as the current collector.<sup>2</sup> (a) low and (b) high resolution FESEM images of VTX80 electrode after the electrochemical analysis. The 3D interconnected structure of VTe<sub>2</sub> and MXene is intact after the electrochemical analyses.



Figure S11: Plot of total density of states of VTe<sub>2</sub> bulk.



**Figure S12**: (a) Optimized structure of VTe<sub>2</sub>/FG-MXene, (b) total DOS for the proposed model heterostructure and (c) Variation of quantum capacitance against applied electrode potential. Blue, green and pink spheres denote the oxygen, hydrogen and fluorine atoms respectively.



**Figure S13**: Characterization of the synthesized  $MoS_2/MX$ ene heterostructure used as the negative electrode. (a) The XRD pattern of  $MoS_2/MX$ ene heterostructure showed XRD reflections corresponds to the JCPDS card 37-1492 of  $MoS_2$ .<sup>3</sup> The (002) peak of  $Ti_3C_2$  MXene has shifted from 8.8° to 6.4° indicating an increment in the interlayer spacing for the heterostructure similar to  $VTe_2/MX$ ene heterostructure.<sup>4</sup> The presence of  $TiO_2$  is observed in the heterostructure is due to the surface oxidation of MXene.<sup>5</sup> (b, c) FESEM images of  $MoS_2/MX$ ene reveals a 3D interconnected heterostructure similar to  $VTe_2/MX$ ene. It clear from the FESEM images that MXene is acting as the growth template for the growth of  $MoS_2$  nanosheets.<sup>6</sup>



Figure S14: Three electrode measurements of  $MoS_2/MX$ ene heterostrcture (a) cyclic voltammogram of  $MoS_2/MX$ ene performed in a potential window of -0.2 - -1.0 V in different scan rates and (b) GCD curves of  $MoS_2/MX$ ene in varying specific currents.



**Figure S15**: (a) Specific capacitance vs specific current plot of the ASC and (b) Nyquist plot of the ASC.

## References

- Y. Shao, M. F. El-Kady, J. Sun, Y. Li, Q. Zhang, M. Zhu, H. Wang, B. Dunn and R. B. Kaner, *Chem. Rev.*, 2018, **118**, 9233–9280.
- 2 S. R. K A, S. Adhikari, S. Radhakrishnan, P. Johari and C. S. Rout, Nanotechnology,

2022, **33**, 295703.

- B. Kirubasankar, M. Narayanasamy, J. Yang, M. Han, W. Zhu, Y. Su, S. Angaiah and
  C. Yan, *Appl. Surf. Sci.*, 2020, 534, 147644.
- X. Wang, H. Li, H. Li, S. Lin, W. Ding, X. Zhu, Z. Sheng, H. Wang, X. Zhu and Y.
  Sun, *Adv. Funct. Mater.*, 2020, **30**, 1–11.
- S. Raj KA, P. Mane, S. Radhakrishnan, B. Chakraborty and C. S. Rout, ACS Appl.
  Nano Mater., 2022, 5, 4423–4436.
- H. Li, X. Chen, E. Zalnezhad, K. N. Hui, K. S. Hui and M. J. Ko, *J. Ind. Eng. Chem.*, 2020, 82, 309–316.